

2/29/04

12/18/04

L21 ANSWER 1 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 2003:868614 CAPLUS  
 DN 139:371877  
 TI Positive-working resist composition  
 IN Sasaki, Tomoya; Mizutani, Kazuyoshi; Kanna, Shinichi  
 PA Fuji Photo Film Co., Ltd., Japan  
 SO Jpn. Kokai Tokkyo Koho, 60 pp.  
 CODEN: JKXXAF

DT Patent  
 LA Japanese

FAN. CNT 2

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2003316007	A2	20031106	JP 2002-126433	20020426
	US 2003232277	A1	20031218	US 2003-422789	20030425
PRAI	JP 2002-126433	A	20020426		
	JP 2002-223234	A	20020731		
	JP 2002-223386	A	20020731		

AB The pos.-working resist composition comprises a resin which increases its solubility

in an alkali developer upon reaction with an acid and has  $\geq 1$  repeating unit selected from I and II (R1,2 = H, halo, cyano, etc.; L1 = divalent bonding group; m1, m2 = 0, 1; R3,4 = alkyl, aryl, etc.; Rb = H, organic group, halo; l = 0-3; and L2 = single bond, divalent bonding group) and  $\geq 1$  repeating unit such as III (R11-16 = H, alkyl, etc.), a compound generating an acid upon receiving an active ray or a radiation. The use of the resin exhibited high optical transparency at  $\leq 160$  nm.

IT 622840-85-1 622840-98-6

RL: TEM (Technical or engineered material use); USES (Uses)  
 (resin in pos.-working resist composition)

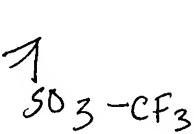
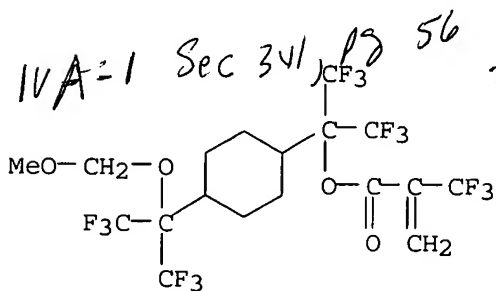
RN 622840-85-1 CAPLUS

CN 2-Propenoic acid, 2-(trifluoromethyl)-, 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-(methoxymethoxy)-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl ester, polymer with 1-methylethyl 4-ethenylbenzenesulfonate (9CI) (CA INDEX NAME)

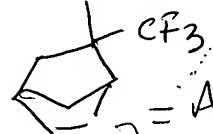
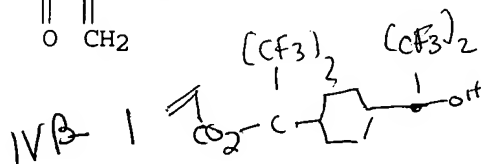
CM 1

CRN 610301-02-5  
 CMF C18 H17 F15 O4

Sec. 143, Cal. 13



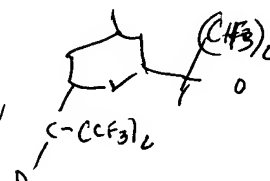
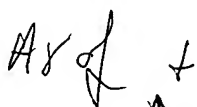
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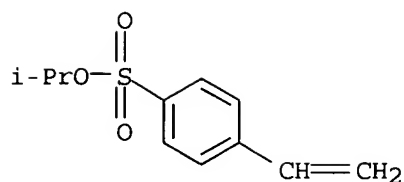


CM 2

CRN 79293-23-5  
 CMF C11 H14 O3 S

my case sec. 60 pg 9  
 A + CO<sub>2</sub>

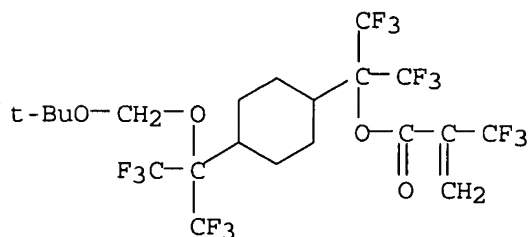




RN 622840-98-6 CAPLUS  
 CN 2-Propenoic acid, 2-(trifluoromethyl)-, 1-[4-[1-[(1,1-dimethylethoxy)methoxy]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl]cyclohexyl]-2,2,2-trifluoro-1-(trifluoromethyl)ethyl ester, polymer with methyl 4-ethenylbenzenesulfonate and 2,2,2-trifluoro-1-[4-[2,2,2-trifluoro-1-hydroxy-1-(trifluoromethyl)ethyl]cyclohexyl]-1-(trifluoromethyl)ethyl 2-(trifluoromethyl)-2-propenoate (9CI) (CA INDEX NAME)

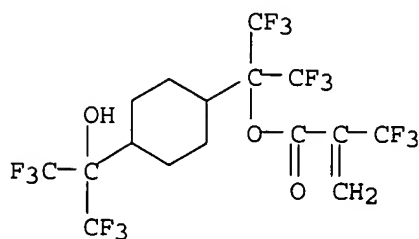
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CRN 622840-97-5  
 CMF C21 H23 F15 O4



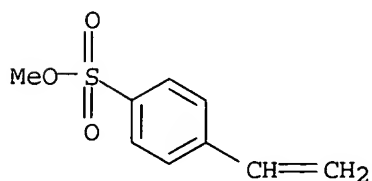
CM 2

CRN 479072-83-8  
 CMF C16 H13 F15 O3



CM 3

CRN 16736-97-3  
 CMF C9 H10 O3 S



L21 ANSWER 2 OF 2 CAPLUS COPYRIGHT 2005 ACS on STN  
 AN 2001:372174 CAPLUS  
 DN 134:368010  
 TI UV-absorbing polymers bearing 2-hydroxybenzophenone or  
 2'-hydroxyphenylbenzotriazole residues  
 IN Aoyama, Masato  
 PA Mitsubishi Chemical Corp., Japan  
 SO Jpn. Kokai Tokkyo Koho, 6 pp.  
 CODEN: JKXXAF  
 DT Patent  
 LA Japanese  
 FAN.CNT 1

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 2001139640	A2	20010522	JP 1999-321992	19991112
PRAI	JP 1999-321992		19991112		

AB The polymers, exhibiting high water solubility and being useful for UV stabilizers especially in waterborne emulsion coatings, comprise (i) UV-absorbing vinylic monomers bearing 2-hydroxybenzophenone or 2'-hydroxyphenylbenzotriazole residues and (ii) water-soluble vinylic monomers bearing anion-dissociative groups. The monomer (ii) may be 2-acrylamidopropanesulfonic acid, 2-acrylamido-2-methylpropanoic acid, 3-acrylamido-2,4,4-trimethylpentanesulfonic acid, 2-acrylamido-2-(4-tolyl)ethanesulfonic acid, 4-styrenesulfonic acid, and/or their salts. Thus, 1:3 (g) 2-hydroxy-4-(2-methacryloyloxy)ethoxybenzophenone-sodium p-styrenesulfonate copolymer showed water solubility  $\geq 25\%$ , no gelation in blending with Rikabond ES 52 (anionic aqueous emulsion coating), and  $< 380\text{-nm}$  UV absorption.

IT **339994-71-7**  
 RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)  
 (macromol. UV absorbers bearing benzophenone or benzotriazole groups and showing good solubility to anionic aqueous coatings)

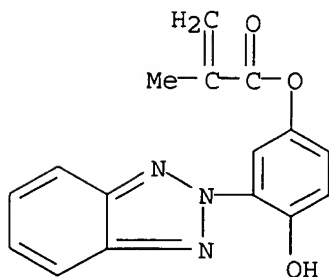
RN 339994-71-7 CAPLUS

CN 2-Propenoic acid, 2-methyl-, 3-(2H-benzotriazol-2-yl)-4-hydroxyphenyl ester, polymer with sodium 4-ethenylbenzenesulfonate (9CI) (CA INDEX NAME)

CM 1

CRN 132288-91-6

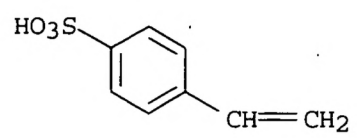
CMF C16 H13 N3 O3



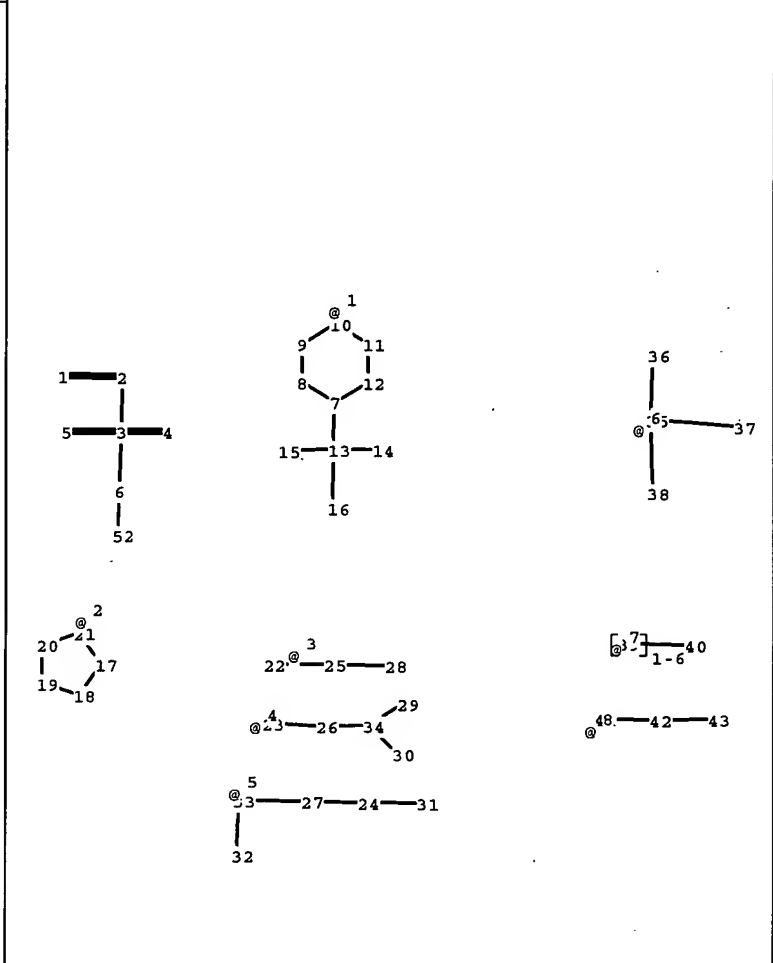
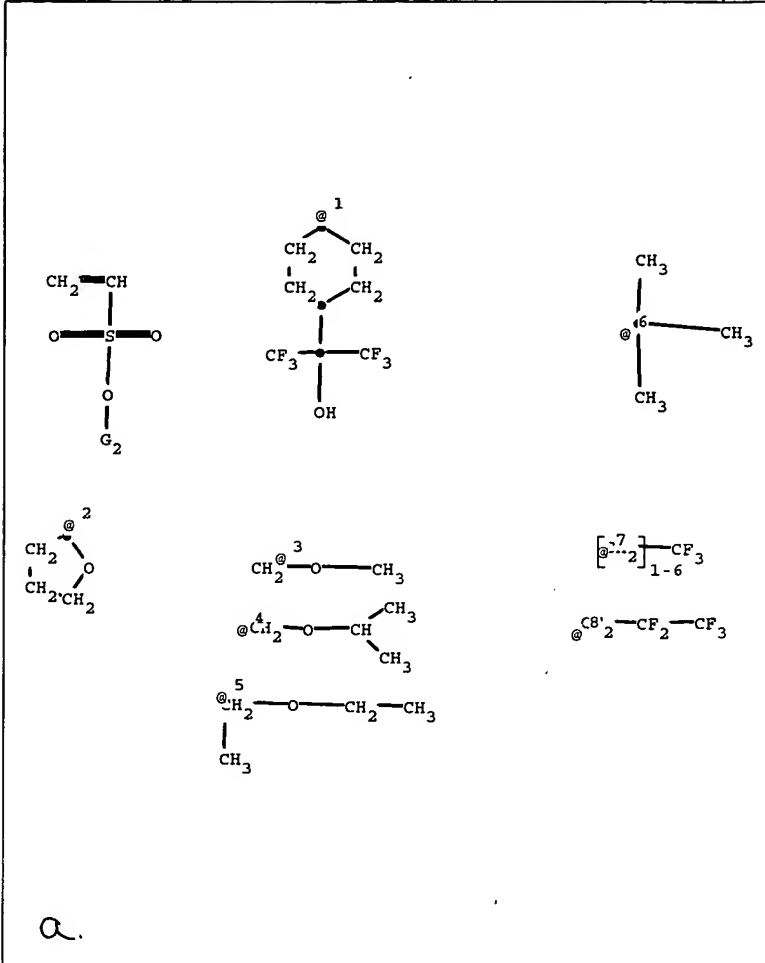
CM 2

CRN 2695-37-6

CMF C8 H8 O3 S . Na



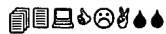
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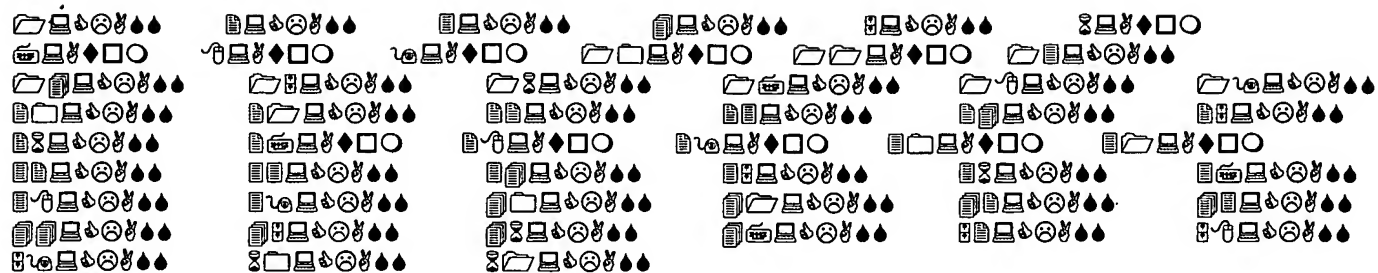






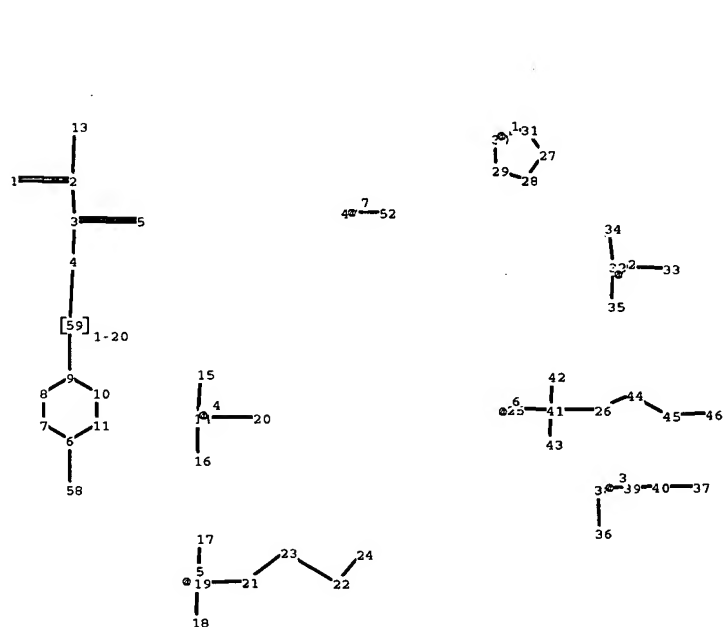






Chemical structures 1 through 7 are shown below:

- 1: A vertical chain starting with a  $\text{CH}_2$  group bonded to a carbon atom labeled  $G_1$ . This carbon is also bonded to a carbonyl group ( $\text{C}=\text{O}$ ) and an oxygen atom. The oxygen atom is bonded to a  $[\text{CH}_2]_{1-20}$  chain, which is then bonded to a cyclobutane ring. The cyclobutane ring has four  $\text{CH}$  groups. The bottom carbon of the ring is bonded to a group labeled  $G_3$ .
- 2: A central carbon atom bonded to two methyl groups ( $\text{CH}_3$ ) and a  $\text{CH}_2$  group. The  $\text{CH}_2$  group is part of a chain that ends in another methyl group ( $\text{CH}_3$ ).
- 3: A central carbon atom bonded to two methyl groups ( $\text{CH}_3$ ) and a  $\text{CH}_2$  group. The  $\text{CH}_2$  group is part of a chain that ends in another methyl group ( $\text{CH}_3$ ).
- 4: A central carbon atom bonded to two  $\text{CF}_3$  groups and a hydroxyl group ( $\text{OH}$ ).
- 5: A central carbon atom bonded to two  $\text{CF}_3$  groups and a  $\text{CH}_2$  group. The  $\text{CH}_2$  group is part of a chain that ends in another methyl group ( $\text{CH}_3$ ).
- 6: A central carbon atom bonded to two  $\text{CF}_3$  groups and a  $\text{CH}_2$  group. The  $\text{CH}_2$  group is part of a chain that ends in another methyl group ( $\text{CH}_3$ ).
- 7: A central carbon atom bonded to two  $\text{CF}_3$  groups and a  $\text{CH}_2$  group. The  $\text{CH}_2$  group is part of a chain that ends in another methyl group ( $\text{CH}_3$ ).

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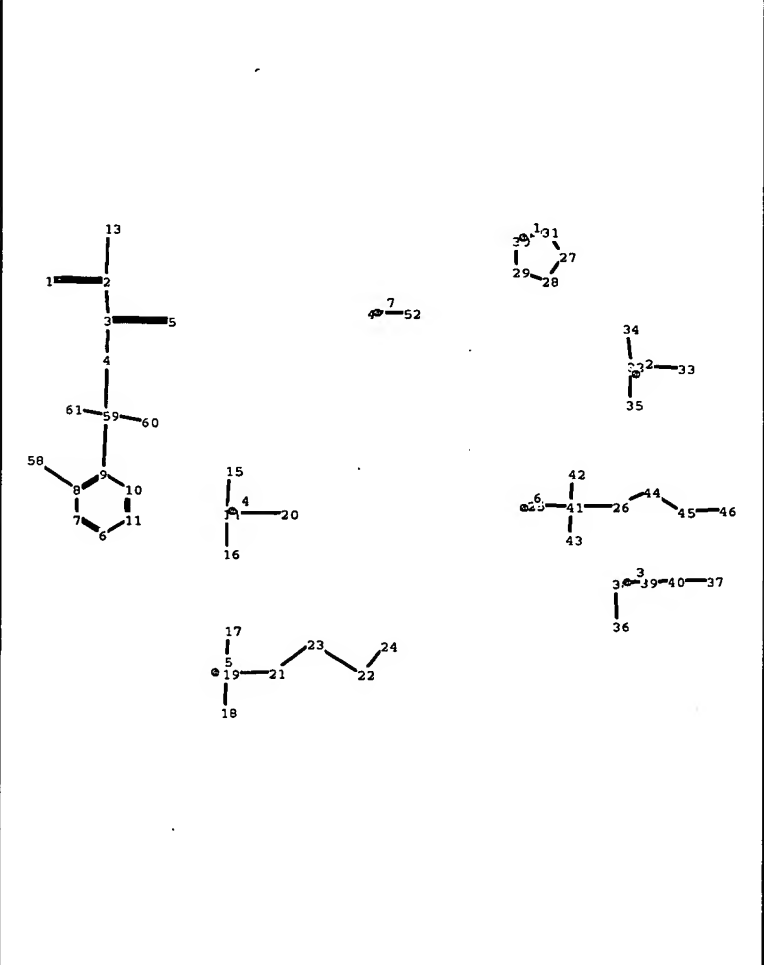
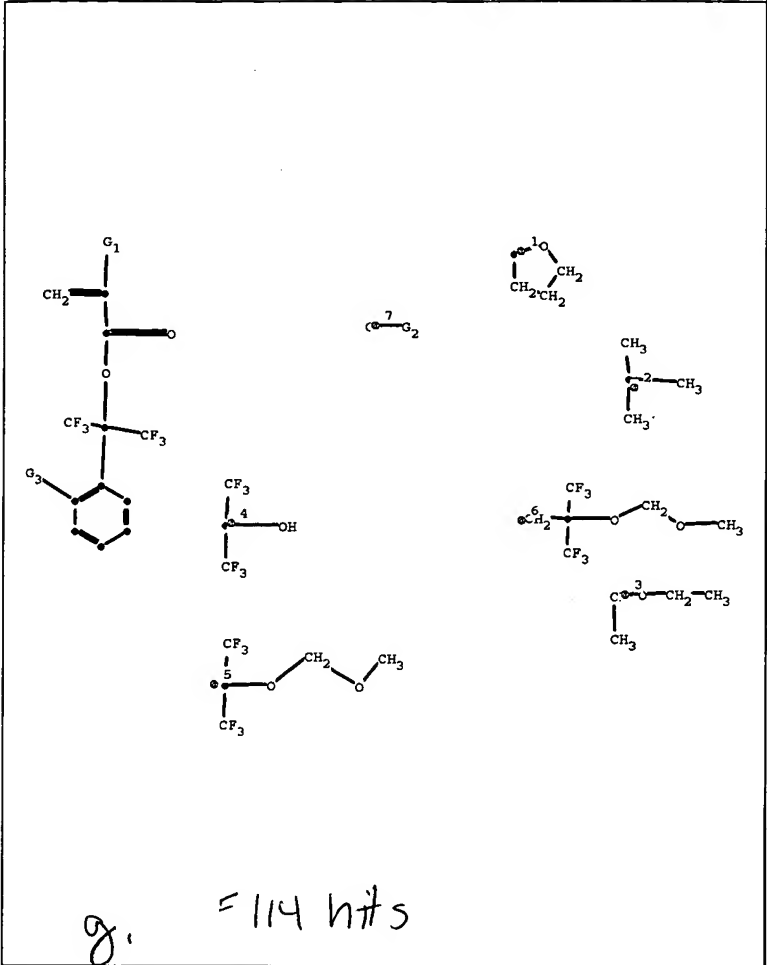










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